

ABSTRACT

SUBSTRATE PROCESSING APPARATUS AND CONTROL METHOD

A substrate processing apparatus which causes a processing tape to abut against a processing object and processes the processing object by a relative movement of the processing tape and the processing object, including: a tape supply reel configured to supply the processing tape; a tape recovery reel configured to recover the processing tape; a recovery motor configured to apply a torque to the tape recovery reel; a tape feed motor configured to feed the processing tape between the tape supply reel and the tape recovery reel; and a control unit configured to control the tape feed motor, wherein the control unit controls the torque of the recovery motor depending on a change in an outer diameter of a roll of the processing tape wound by the tape recovery reel such that tension applied to the processing tape is constant, using a feed length of the tape fed by the tape feed motor and a thickness of the processing tape.

Figure 4